

Notice of References Cited

Application/Control No.

09/652,533

Applicant(s)/Patent Under

Reexamination

SANDHU ET AL.

Examiner

W. David Coleman

Art Unit

2823

Page 1 of 1

U.S. PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
A	US-6,174,377	01-2001	Doering et al.	118/715
B	US-5,916,365	06-1999	Sherman	117/92
C	US-			
D	US-			
E	US-			
F	US-			
G	US-			
H	US-			
I	US-			
J	US-			
K	US-			
L	US-			
M	US-			

FOREIGN PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
N					
O					
P					
Q					
R					
S					
T					

NON-PATENT DOCUMENTS

*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
U	Suntola, "Surface chemistry of materials deposition at atomic layer level", Applied Surface Science, vol. 100/101, March 1996, pp. 391-398.
V	Aarik et al., "Effect of growth conditions on formation of TiO _{sub} 2-II thin films in atomic layer deposition process", Journal of Crystal Growth, Vol. 181, August 1997, pp. 259-264
W	Skarp, "ALE-reactor for large area depositions", Applied Surface Science, vol. 112, March 1997, pp. 251-254.
X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.